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(71)Applicant : HITACHI LTD
HITACHI SETSUBI ENG CO
LTD

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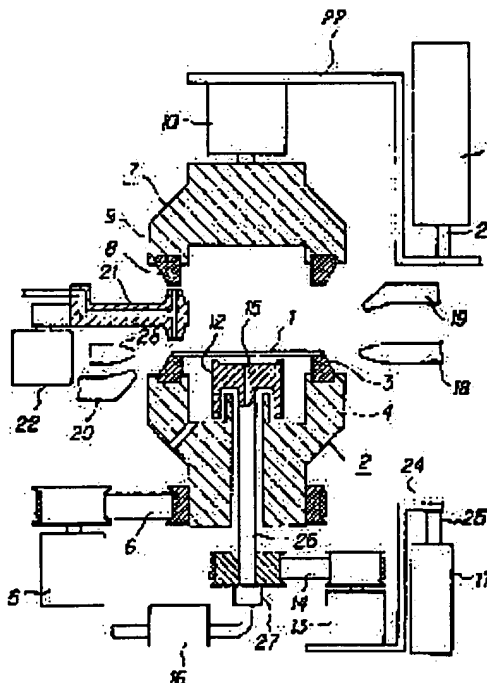
(72)Inventor : KINOSHITA TOMOO
SAISU KOICHI
KANO KIYOTAKA

(54) SEMICONDUCTOR WAFER SEAL ETCHING APPARATUS

(57)Abstract:

PURPOSE: To obtain a semiconductor wafer seal etching apparatus whose degradation due to etchant is prevented and by which a semiconductor wafer is cleaned easily by a method wherein a second small-diameter holder moved up and down with reference to a holder on one side and turned is installed inside the holder.

CONSTITUTION: A second small-diameter holder 12 is arranged at the inner side from a lower-side seal member 3 at a lower holder 2 so as to be rotatable with reference to the lower holder 2. The second holder 12 is fixed to the upper part of a spin shaft 26 which is rotatable with reference to the lower holder 2 so as to be on the same axis as a lower-side rotating body 4. Then, a semiconductor wafer 1 is held to the second holder 12 by a vacuum suction means at an evacuation device 16 so as to be turned at high speed, and ultra-pure water is supplied to the surface and the rear surface of the semiconductor wafer 1 by nozzles 19, 20 so as to be spin-cleaned at high speed. Thereby, it is possible to prevent the degradation of a semiconductor wafer seal etching apparatus due to etchant, and the semiconductor wafer 1 can be cleaned easily.



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